

a1
cont
[said] plasma generation means [is] which generates a plasma [generation means] in which [a] the degree of [said] plasma dissociation is a middle degree and said gas species containing [the] carbon and [the] fluorine is generated fully in the plasma, and a temperature of a region which forms a side wall of said vacuum processing chamber is controlled to have a range of 10 °C to 120 °C.

Claim 2, line 3, after "a" insert --source of--, same line 3, delete "source";

line 4, after "is" insert --in--.

Claim 3, line 4, after "microwave" insert --is provided--.

a2
6. (Amended) In a plasma processing method using a vacuum processing chamber, a sample table for mounting a sample which is processed in said vacuum processing chamber, and a plasma generation means, [the plasma processing method,] wherein [when] a plasma processing is carried out by generating a plasma [according] in response to [an] introduction of a gas which contains at least carbon and fluorine, and [by generating] a gas species is generated which contains a carbon and fluorine according to a plasma dissociation, the plasma processing method comprising the steps of:

Sub 2
[said plasma generation means is] generating a plasma [generation means] in which a degree of [said] plasma dissociation is a middle-degree and said gas species